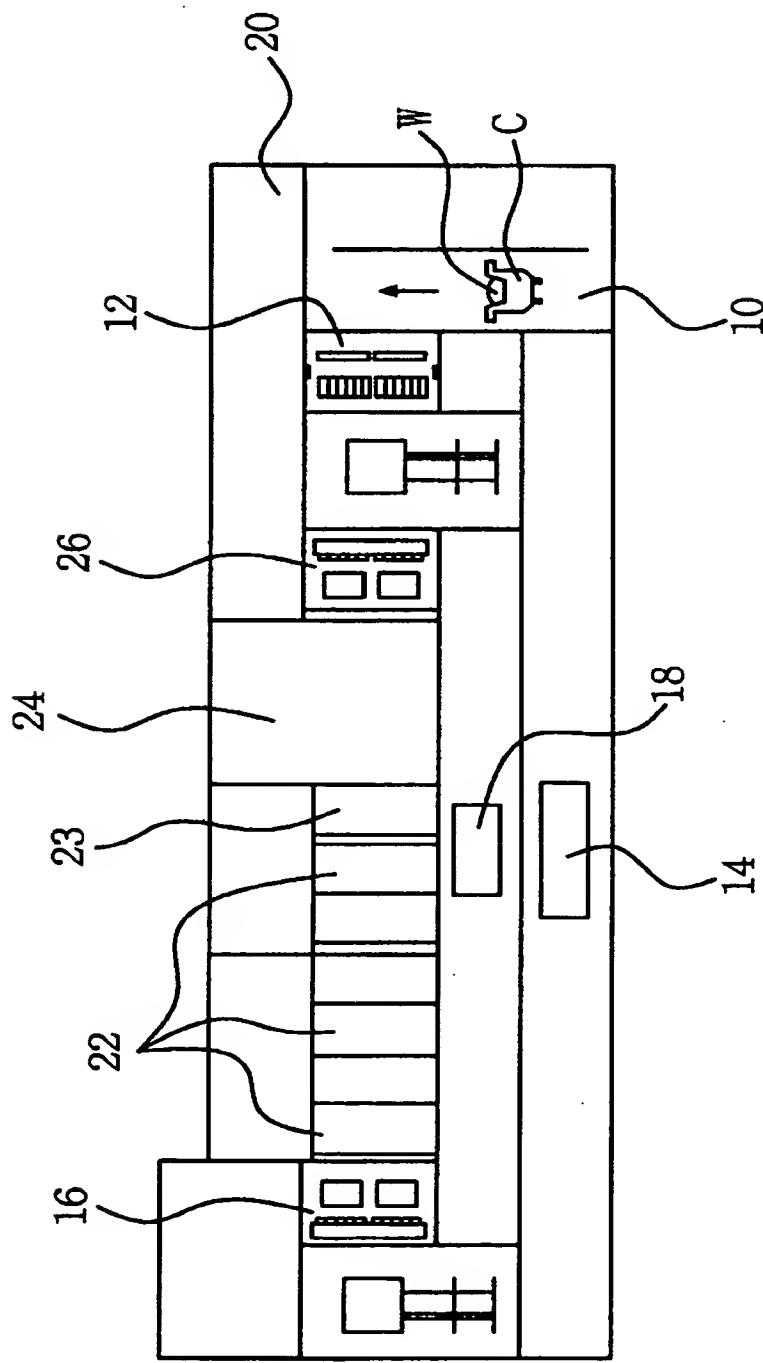


METHOD OF AND APPARATUS FOR CLEANING SEMICONDUCTOR WAFERS

Application No. [NEW] – Attorney Docket No. SEC.1101

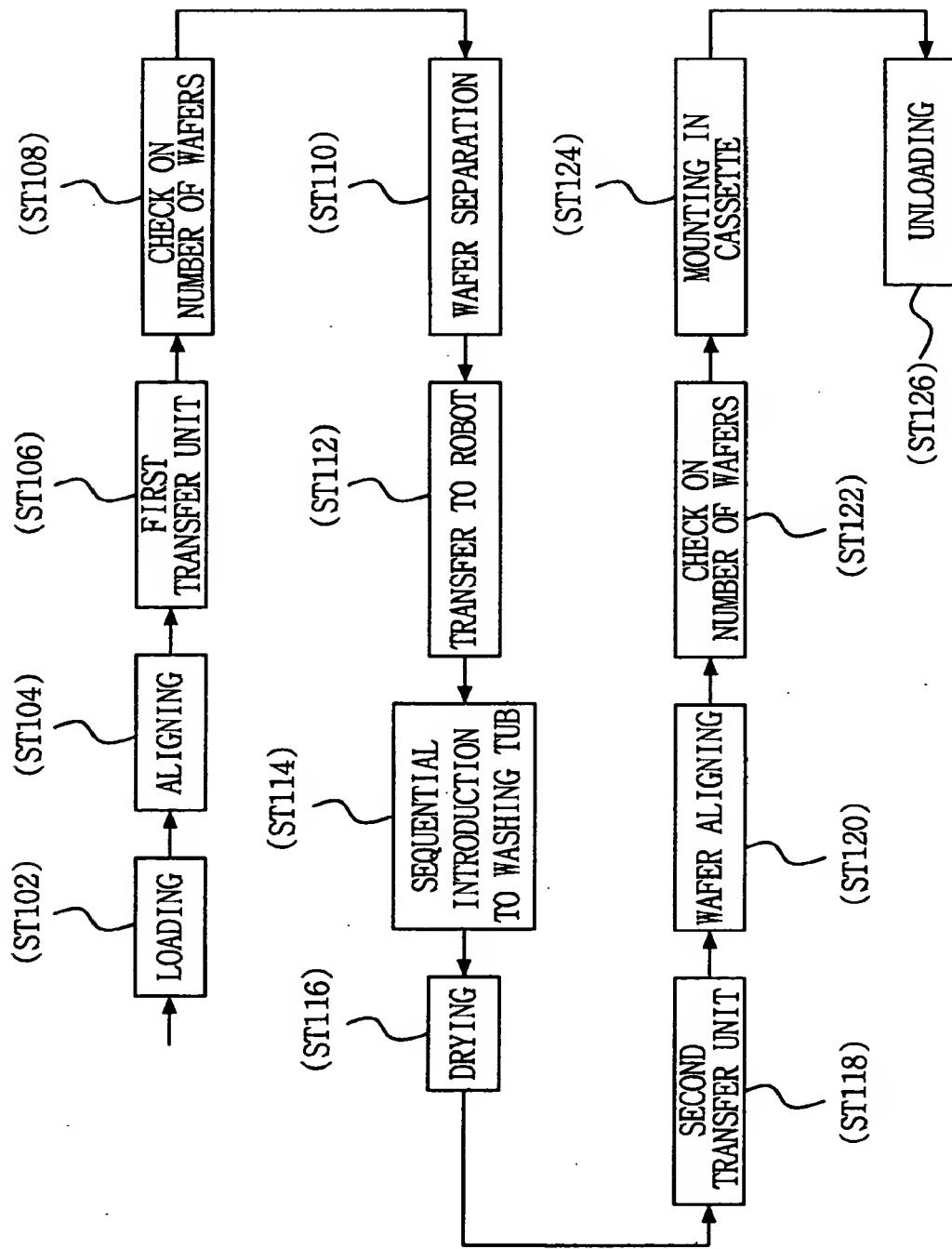
Inventors: Ki-Hwan PARK et al.

FIG. 1 (PRIOR ART)



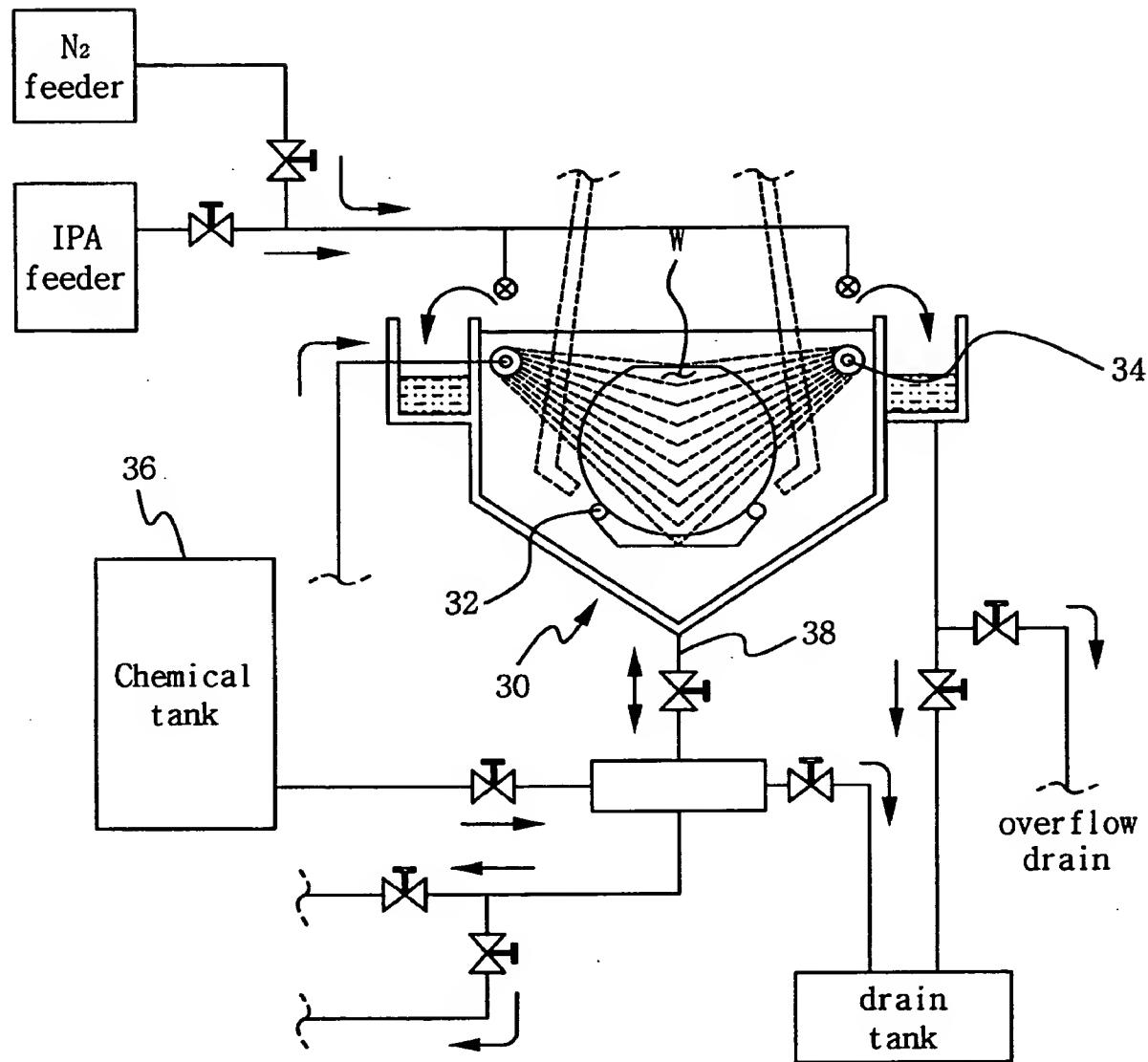
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FIG. 2 (PRIOR ART)



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FIG. 3 (PRIOR ART)

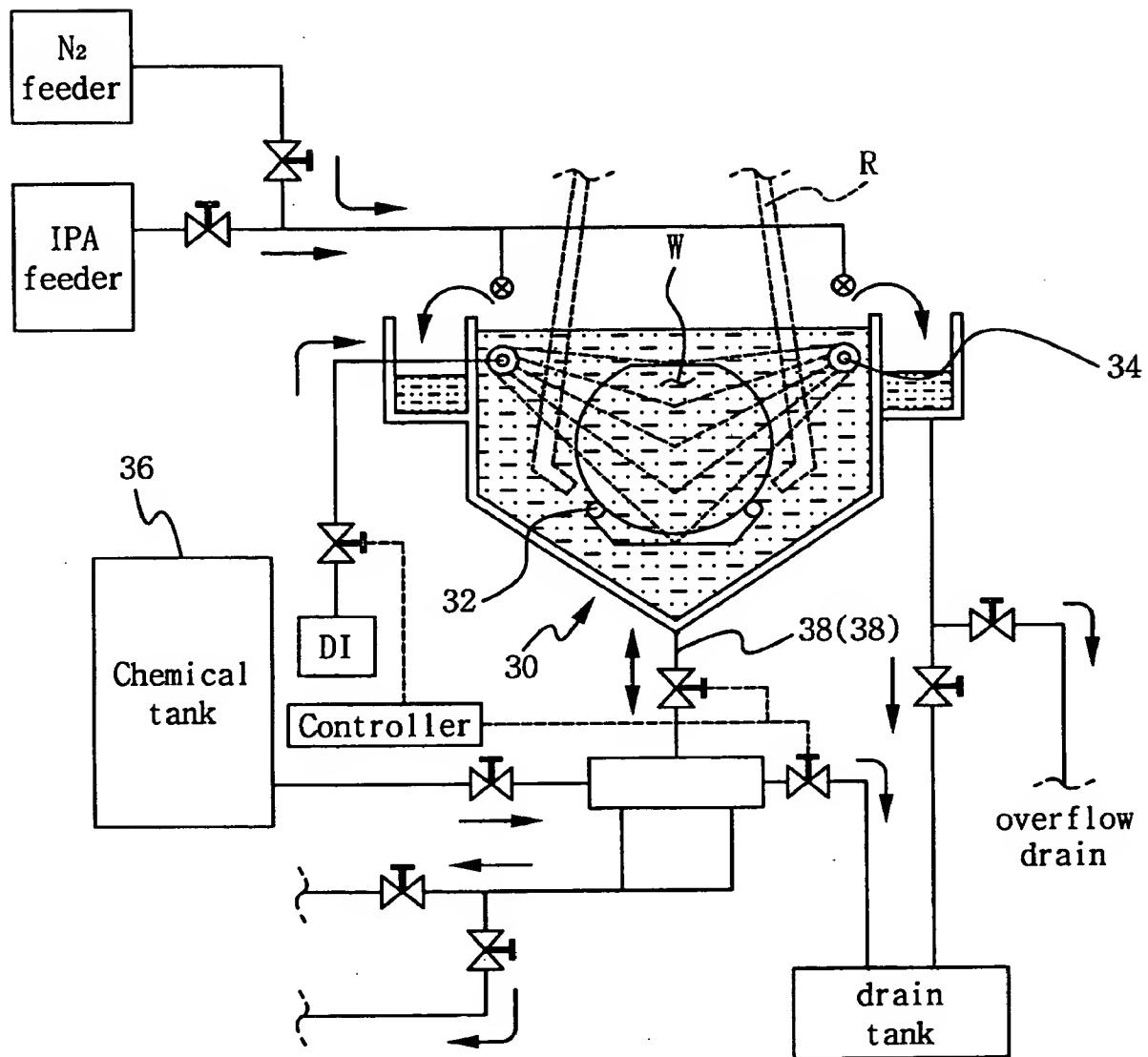


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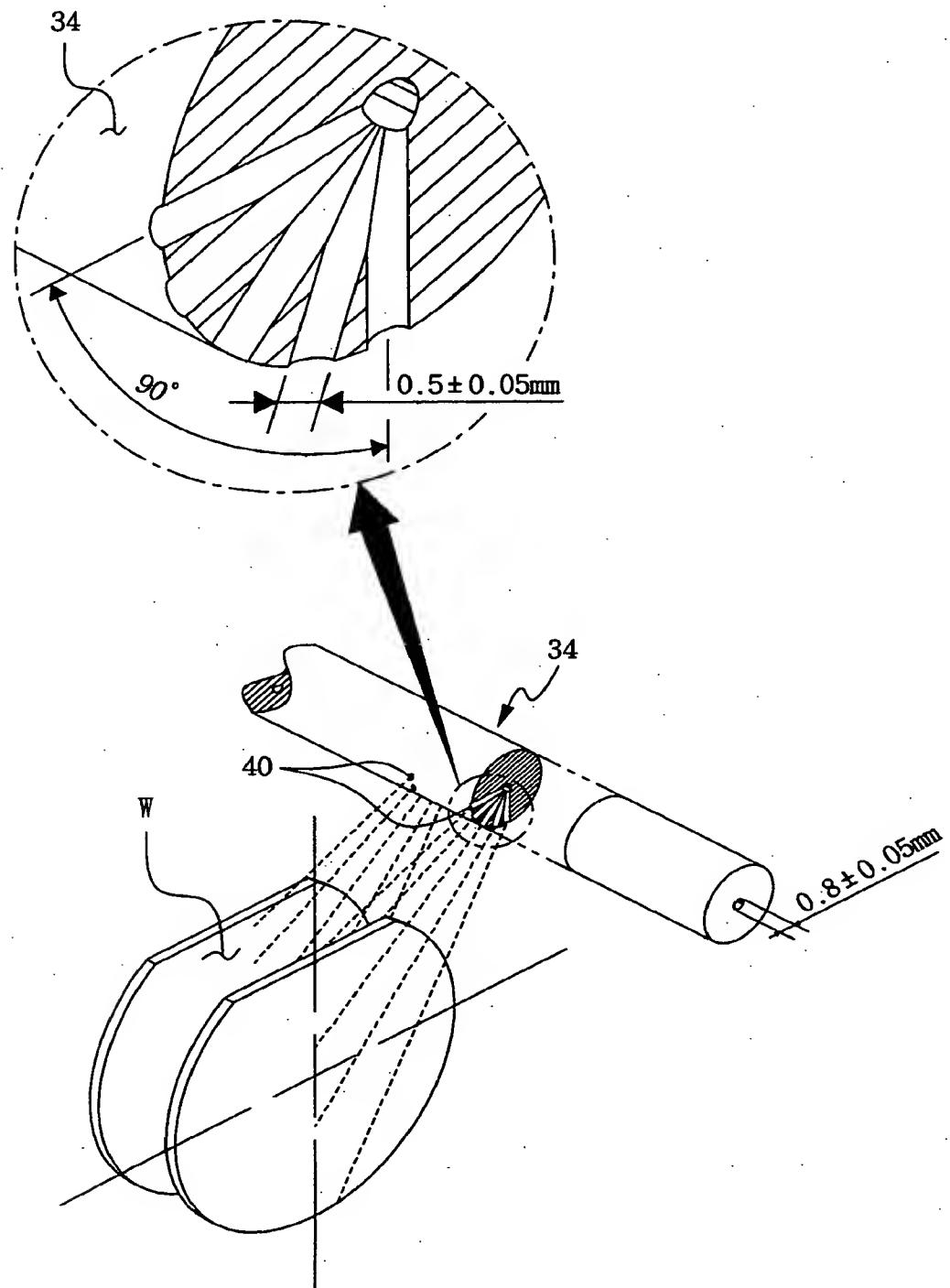
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FIG.4



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FIG. 5



METHOD OF AND APPARATUS FOR CLEANING SEMICONDUCTOR WAFERS

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FIG.6

E/R Difference and Particle Improvement (STANDARD OF 25 WAFERS)

